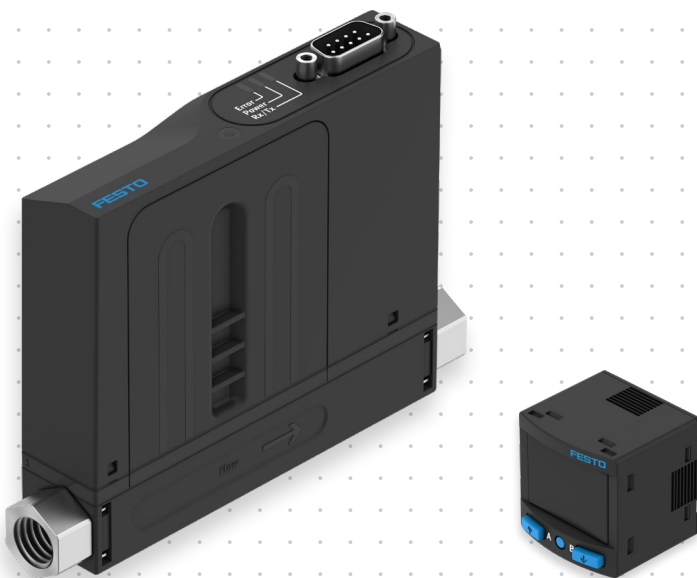




## Mass flow controller VEFC



### Highlights

- Very compact: only 24 mm wide
- Direct-controlled, dynamic piezo valve
- Very light: only 250 g weight
- Monitoring of mass flow and outlet pressure
- Very flexible: customizable control parameters
- Excellent value for money

**The VEFC for inert gases is very compact and has all the advantages of piezo valves: maximum dynamic response, infinite precision, very low power consumption and heat generation, stable flow rate without the need for manual adjustment. All that at a very attractive price/performance ratio.**

#### Extremely compact

At 24 x 109 x 92 mm (W x L x H), the mass flow controller is one of the most compact on the market and has a flow rate of 200 l/min.

#### Intuitive and reliable

The CDSV control panel is the ideal accessory for the VEFC mass flow controller. Its high-contrast LCD display ensures easy viewing and intuitive operation.

#### Everything under control

VEFC is digitalised. This keeps the flow rate constant and eliminates the need for manual adjustment. It only takes milliseconds to precisely adjust the flow rates and their settings, and be tamper-proof. This gives you maximum flexibility in your production processes. The VEFC also provides you with the flow rate and output pressure at the same time, allowing you to continuously monitor the process.

#### The favourable alternative for the semiconductor industry

The mass flow of inert gases such as nitrogen must be reliably controlled, especially in the semiconductor industry, in order to avoid defects on wafers. With its focus on inert gases without media separation, VEFC is ideal for controlling nitrogen in load ports or EFEMs – and at an unbeatable price.



#### Additional information:

Product pages

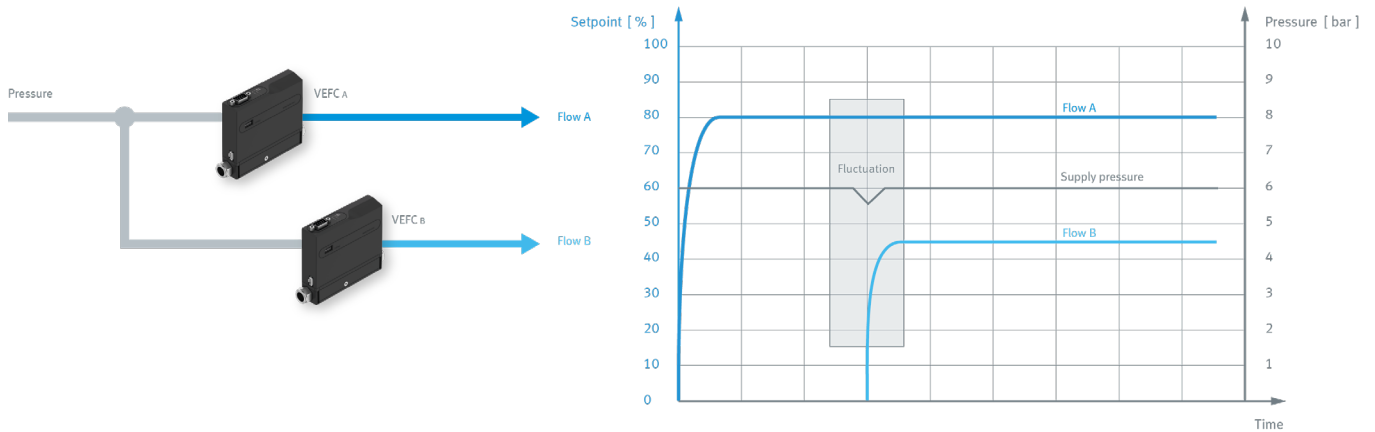
- > [www.festo.com/catalogue/vefc](http://www.festo.com/catalogue/vefc)
- > [www.festo.com/catalogue/cdsv](http://www.festo.com/catalogue/cdsv)



### Using the pressure difference method

The mass flow controller VEFC works with the pressure difference method. In combination with piezo technology, flow rates

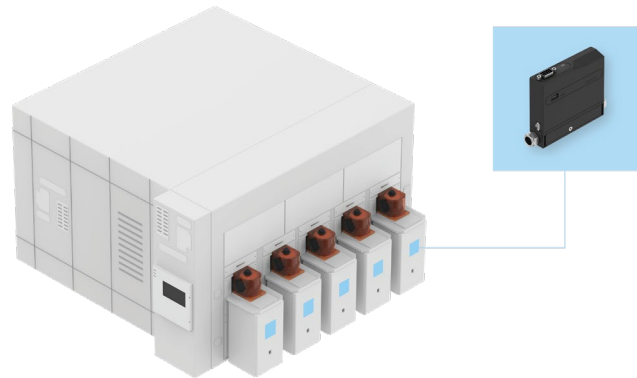
can be controlled very quickly, dynamically and insensitively to pressure fluctuations.



### Economical, reliable and precise N<sub>2</sub> purging

A wide variety of flows can be regulated in the individual purge steps with VEFC in the load port. It ensures that only the absolutely necessary amount of nitrogen is used, whether during pre-blowing, pre-purge, process purge and post-purge.

This saves nitrogen and shortens the process time until the dry shielding gas atmosphere is reached.



### Technical data

#### VEFC

Media	Compressed air 7.4.4./CDA, inert gases (N <sub>2</sub> , Ar, etc.)
Standard conditions	DIN 1343; SEMI E12 corresponding – N <sub>2</sub> equivalent
Flow rate	50, 100, 200 slm
Supply pressure	0.6 MPa
Accuracy of flow rate	± 1.5 % FS
Repetition accuracy	± 0.2 % FS
Step response time	< 500 ms
Electrical connection	Analogue, RS485
Valve technology	Piezo technology
Measuring principle	Pressure difference method
Pneumatic connection	Rc1/4, G1/4, QS or external thread with metal seal on the front
Operating voltage	24 V
Protection class	IP20